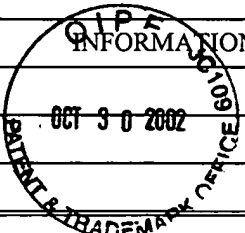


U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-11549US		10/085,498	
 INFORMATION NON DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)					Applicant(s)			
					Woo Sik Yoo			
					Filing Date		Group	
					February 26, 2002		Unassigned	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
KCF	AA	5,985,364	11/16/99	Smith et al.	427	240		
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	AF							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	AG							
	AH							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
KCF	AI	Gene Li, "Total Solutions for Front-End Thermal Processing" Foresight May 2001, pages 41-45						
KCF	AJ	A. Karamcheti et al., "Silicon Oxynitride Films As A Segue To The High-K Era" Semiconductor Fabtech, 12 th Edition, pages 207-214. (No date)						
KCF	AK	S. Wolf and R.N. Tauber, "For the VLSI Era Volume 1-Process Technology" Silicon Processing for the VLSI Era, pages 164-194. (No date)						
KCF	AL	Peter Van Zant, "Microchip Fabrication, A Practical Guide to Semiconductor Processing" Fourth Edition, Chapter Twelve, pages 364-393. (No date)						
Examiner		Kirsten Colley						
		Date Considered		9/8/03				
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